

AMENDMENTS TO THE CLAIMS

The following listing of claims will replace all prior versions of claims in the application.

1. (Currently amended) A heat resistant masking tape, comprising (1) a heat resistant backing film layer, wherein ~~a surface of~~ the heat resistant backing film layer is ~~surface treated~~ selected from the group consisting of polyethylene naphthalate, polyphenylene sulfide, and polyimide; and (2) a nonaqueous pressure-sensitive adhesive layer disposed on ~~the treated a~~ surface of the heat resistant backing film layer, wherein the pressure-sensitive adhesive layer comprises a polymer resulting from polymerizing and cross-linking a ~~nonaqueous~~ monomer mixture comprising an alkyl (meth)acrylate with an alkyl group having 4 to 15 carbon atoms, glycidyl(meth)acrylate and (meth)acrylic acid, the glycidyl(meth)acrylate being present in an amount of 2 to 13% by weight of the total weight of monomers and the (meth)acrylic acid being present in an amount of 1 to 7% by weight of the total weight of monomers.

2. (Original) A heat resistant masking tape according to claim 1, wherein said pressure-sensitive adhesive layer has a thickness of 0.5 to 100 μm .

3. (Cancelled)

4. (Previously presented) A heat resistant masking tape according to claim 1, wherein said heat resistant backing layer has a thickness of 1 to 250 μm .

5. (Previously presented) A heat resistant masking tape, comprising (1) a heat resistant backing film layer; and (2) a pressure-sensitive adhesive layer disposed on the heat resistant backing film layer, wherein the pressure-sensitive adhesive layer comprises a polymer resulting from polymerizing and cross-linking a monomer mixture consisting essentially of an alkyl (meth)acrylate with an alkyl group having 4 to 15 carbon atoms, glycidyl(meth)acrylate and (meth)acrylic acid, the glycidyl(meth)acrylate being present in an amount of 2 to 13% by weight of the total weight of monomers and the (meth)acrylic acid being present in an amount of 1 to 7% by weight of the total weight of monomers.